


INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Docket: 23-59123		App: 09/905.654	
				Applicant: Josephson et al.			
				Filed: July 11, 2001		Art Unit: 1725	
U.S. PATENT DOCUMENTS							
Init.*	Number	Date	Name	Class	Sub	Filed	
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11	5,187,344	02/16/1993	Mizuno et al.	—	—		
12	5,817,284	10/09/1998	Nakano et al.	—	—		
13	5,980,701	11/09/1999	Sharma et al.	—	—		
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16			Evans et al., "Plasma remediation of trichloroethylene in silent discharge plasmas," <i>J. Appl. Phys.</i> 74:9 pp. 5378-5387 (1993)				
17			Flippo et al., Abatement of Fluorine Emissions Utilizing an ATMI CDO™ Model 863 with Steam Injection (2001)				
18			Grothaus et al., "Harmful Compounds Yield to Nonthermal Plasma Reactor," <i>SwRI Technology Today</i> , http://www.swri.org , pp. 1-9 (published in <i>Technology Today</i> , Spring 1996)				
19			International Sematech Disclosure, "Evaluation of a Litmas "Blue" point-of-Use (POU) Plasma Abatement Device for Perfluorocompound (PFC) Destruction," Technology Transfer No. 98123605A-Eng (December 15, 1998)				
EXAMINER: <i>AMM</i>				DATE: <i>11/19/05</i>			
*Examiner: Initial if considered, whether or not in conformance with MPEP 609; draw line through cite if not in conformance and not considered. Send copy.							

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CU			Lester, "Clean Processing. No More PFC Emissions in Plasma Chamber Cleaning?" <i>Semiconductor</i> , p. 46 (2000) <i>no note</i>				
CU			Rosenthal et al., "Corona Discharge for Surface Treatment," <i>IEEE Trans. Ind. Appln.</i> , I-5, 328-335 (1975) <i>no note</i>				
CU			Timms et al., "The chemistry of volatile waste from silicon wafer processing," <i>J. Chem. Soc.</i> , pp. 815-822 (1999) <i>no note</i>				
CU			Vartanian et al., "Plasma Abatement Reduces PFC Emission," <i>Semiconductor International</i> , pp. 191-198 (2000) <i>no note</i>				
EXAMINER: <i>mm m m</i>				DATE: <i>11/18/03</i>			
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Docket: 23-59123			
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U.S. PATENT DOCUMENTS							
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OTHER DOCUMENTS							
EXAMINER: <i>u m m</i>				DATE: <i>11/19/03</i>			
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